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Depositor: Karen Cing-Mars

Karen Cing-Mars 8/12/03  
(Signature & date)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of : August 12, 2003  
Hendrik F. Hamann et al. : Group Art Unit:  
Serial No. 10/604,487 : Examiner:  
Filed: 07/25/2003 : International Business Machines Corporation  
2070 Route 52  
Hopewell Junction, NY 12533

**TITLE: SYSTEMS AND METHODS OF ALTERING A VERY SMALL SURFACE AREA**

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

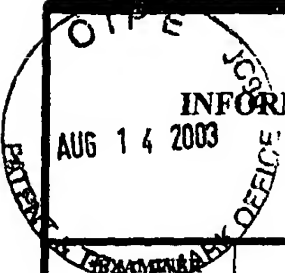
Pursuant to the duty of disclosure set forth in 37 C.F.R. 1.56, and further pursuant to the provisions of 37 C.F.R. 1.97 and 1.98, applicants hereby respectfully submit copies of the prior patents and publications as listed on Form PTO-1449, attached hereto.

In citing these documents, no representation is made nor intended as to the pertinency or non-pertinency of the art, that better art than that listed is not available, or that other art is not applicable.

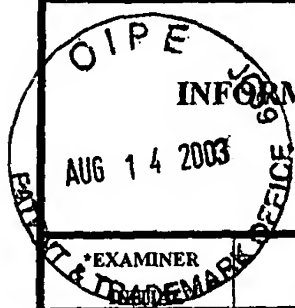
Respectfully submitted,  
Hendrik F. Hamann et al.

BY

Steven Capella  
Steven Capella, Attorney  
Registration No. 33,086  
Telephone No. 845-894-3669

 <b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)		Docket Number (Optional) <b>FIS920020166US1</b>	Application Number <b>10/604,487</b>
		Applicant(s) <b>Hendrik F. Hamann et al.</b>	
		Filing Date <b>07/25/2003</b>	Group Art Unit
<b>OTHER DOCUMENTS</b> (Including Author, Title, Date, Pertinent Pages, Etc.)			
INITIAL		A Nanoplotter with Both Parallel and Serial Writing Capabilities, Seunghun Hong and Chad A. Mirkin, Science Magazine, Vol. 288, June 9, 2000	
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		AFM Single & Dual Wire Thermal & Electrochemical Glass Sensors & Heaters, Nanonics Imaging Ltd., <a href="http://www.nanonics.co.il">www.nanonics.co.il</a> August 16, 2001.	
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		Strength of Electric Field in Apertureless Near-Field Optical Microscopy, Yves C. Martin et al., IBM Research Report, RC21891 (98484) 11/9/2000.	
		Scanning Electron Microscope Using Atomically Fine Field Emission Tip, P.E. Batson et al., YO8880445, IBM Technical Disclosure Bulletin, Vol. 37, No. 10, October 1994.	
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		Etched Microcavities for Mechanical Clamping of Atomic Force Sensors, T. Bayer et al. GE8960053, IBM Technical Disclosure Bulletin, Vol 40, No. 04, April 1997.	
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		Self-Assembly of Ink Molecules in Dip-Pen Nanolithography: A Diffusion Model, Joonkyung Jang et al., Journal of Chemical Physics, Vol. 115, No. 6, 8/8/2001.	
EXAMINER		DATE CONSIDERED	
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			

<div style="display: flex; align-items: center; justify-content: center;"> <div style="border: 1px solid black; border-radius: 50%; padding: 10px; margin-right: 10px; text-align: center;"> O I P E  AUG 14 2003  EXAMINER  TRADEMARK OFFICE </div> <div> <b>INFORMATION DISCLOSURE CITATION</b>  <i>(Use several sheets if necessary)</i> </div> </div>		Docket Number (Optional)	Application Number	
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OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>				
		Dip-Pen Nanolithography on Semiconductor Surfaces, Albena Ivanisevic et al., J. Am. Chem. Soc. 2001, 123, 7887-7889.		
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**OTHER DOCUMENTS** *(Including Author, Title, Date, Pertinent Pages, Etc.)*

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Technology of Proximal Probe Lithography, Christie R.K. Marrian, Naval Research Laboratory, SPIE Institutes, Volume IS 10, 1993.

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